

Notice of References Cited	Application/Control No. 10/790,606	Applicant(s)/Patent Under Reexamination LU, JIONG-PING	
	Examiner Long K. Tran	Art Unit 2818	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,846,734	01-2005	Amos et al.	438/592
*	B	US-6,534,871	03-2003	Maa et al.	257/769
*	C	US-6,686,274	02-2004	Shimazu et al.	438/653
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	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Hong-Xiang Mo et al., Formation and Properties of ternary silicide (CoxNi1-x)Si2 thin films, 1998 IEEE, 0-7803-4306-9/98, pages 271- 274.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.